

Analog Integrated Circuits
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Lecture - 10
Random Mismatch

In this lecture we will look at the other type of the second type of mismatch called random mismatch. So, we will start first start off with an example device of a Capacitor.

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RANDOM MISMATCH

Statistical distribution

$C_{nom} \propto W \cdot L$

as $W \uparrow \Rightarrow \frac{\Delta W}{W} \& \frac{\Delta L}{L} \downarrow$
as $L \uparrow \Rightarrow \text{"} \neq \text{"} \downarrow$

- 1) Use devices with large area
- 2) There is a process dependent effect
- 3) Use circuit techniques to mitigate random mismatch

NPTEL

So, let us say that the capacitor has a certain width and length, it is a basically I am showing the top view of the capacitor. So, the this is the top plate of the capacitor, and of course, the capacitance value depends on the area. Now it turns out that if you actually zoom into the edges, what you will find this that the edges at some level are not going to be completely regular. And they are there is going to be some small variation and of course, this variation will be completely random.

so in fact, one of the things that sets apart random mismatch from systematic mismatch is the fact that there is some statistical distribution. So, there is some statistical dependence of this of all or many circuit parameters. Now let us come back to this example because this value now or rather this capacitance now has some variation and it is edge at some microscopic level, you can talk about a nominal value of capacitance which depends on the area of the plate. So, the nominal C_{nom} is proportional to w times L , but the actual

value of the capacitance will be slightly different depending on the you know distribution of these defects.

So, therefore, you now need to find a way to figure out how this is going to effective. So, let me say that there is going to be some L plus ΔL here. So, I will show that in blue, and this is going to have w plus Δw , and in other words if I take 2 of these devices 2 capacitors may be on the same ic or across ics, I will find that this value of Δw and ΔL has a certain distribution. And this particular distribution right will most probably be we will have a Gaussian distribution, but one particular device capacitor may have a particular value of Δw and ΔL , if I take a different device I could have a completely different value.

Now, I need to find out a way to minimize this value of ΔL n Δw , it turns out if you just do a statistical analysis of this particular structure for example, you could slice this into very small strips either in the vertical direction or the horizontal direction, you will find that the value when you increase the value of the width. In other words let us say you do not do anything to the length and you increase the value of the width it turns out there is some type of averaging effect on both Δw and ΔL . So, it turns out that if you do this Δw by w and data L by L both decrease.

Similarly, you will see the same effect if you increase the value of the length of the plate also right. So, this means of course, that if you want to reduce the relative value of Δw and ΔL , you have to make sure that the area of the plate is as large as possible. Now in some cases this is; obviously, not easily possible because now you need to find some way to compensate for the increased value of the capacitance. Now I will write the down as maybe 3 points, the first point is if you want to reduce the random mismatch you use devices with large area. Now I have taken the example of a capacitor, but the same is true for a transistor or a resistor or other types of components also.

Now, the second thing I wanted to point out, there is a process dependent effect what do I mean by this? Of course, this is due to microscopic irregularities in the edges. If I do a more finely controlled process or maybe in a different way, I may find that ΔL by L and Δw by w is already smaller to begin with right. So, better process can give you a lower a tighter distribution of the random mismatch component and finally, it is possible to use circuit techniques to mitigate mismatch random mismatch.

Now, you will find that these kinds of effects are much more or magnified, when you start looking at a class of circuits called differential circuits. Now when we come to those kind of circuits we will study the mismatch of the differential circuit. For now we will just take the example of a common source amplifier.

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Example

Random variation in: $R_D, V_T, \mu_n C_{ox}$

$$r_{V_T} = \frac{A_{V_T}}{\sqrt{W \cdot L}} ; r_{\mu_n C_{ox}} = \frac{A_{\mu_n C_{ox}}}{\sqrt{W \cdot L}}$$

$$r_{\frac{dR}{R}} = \frac{A_R}{\sqrt{W \cdot L}} ; r_{\frac{dC}{C}} = \frac{A_C}{\sqrt{W \cdot L}}$$

2-port network

Now, I will assume that the common source amplifier has a resistive load, some resistor R . The input has some bias V_{B1} , let us say this resistor is R_D and the value of the supply voltage is V_{DD} .

Now, what are the parameters that can vary here? The parameters that can vary are the following, if I look simply at low frequencies and I am doing in fact, let us go 1 step further and say I am only going to look at the dc bias point of this circuit. You will find that you could have random variation in R_D . So, you can represent that by some ΔR_D which has a zero mean and some Gaussian distribution, you could have a change in the threshold voltage of the device. So, you might have some ΔV_T in the device you expect the threshold voltage of let us say 500 millivolts, the actual threshold voltage of the device may actually be 490 millivolts or 510 millivolts.

Apart from this 2, you may also have an error in for example, the capacitances associated with the circuit, but we will not look at that. You may also have an error in the $\mu_n C_{ox}$ value. So, let us now write down the expression for the nominal value and the distribution around this, but the point is you will represent those things in terms of

certain standard parameters. So, those standard parameters would be the sigma of the V T, all of these remember will have a process dependent parameter now I am going to call that a V T in this case, and it should be noted that they are inversely proportional to the square root of the area, the sigma is inversely proportional to the square root of the area.

Sigma squared will be proportional to the inverse of the area itself. Sigma Mu n Cox again you can represent that in terms of this parameter A Mu n Cox the variation of resistors and capacitors is usually represented in the relative manner. So, remember that the units of a V T, A Mu n Cox etcetera may not be the same. So, this would be AR over root of w times L and finally, if you had a capacitance, this would be A c over root of w times L what is the effect of having mismatch. Before we do the example let us quickly cover that the effect of having a mismatch on any circuit. So, let us represent that by a by 2 port circuit by 2 port network.

It turns out that this effect can be clubbed some very similar to noise, as a combination of 2 sets of variables a series voltage and a shunt current. And I am going to call that some v o s and ios. Now remember that if I take a particular circuit it may have a particular value of v o s and ios, I need to take a large number of circuits depending on the variation of threshold voltages, resistances etcetera I will see a particular value of input referred offsets v o s and i o s.

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\bar{V}_{os} = input-referred offset voltage
 \bar{I}_{os} = " " " current

- 1) \bar{V}_{os} & \bar{I}_{os} may be correlated
- 2) For uncorrelated quantities : use squared quantities in your analysis

$V_{A_{S1}} = V_{A_{S2}}$
 Assume ΔV_T is small.

The circuit diagram shows a differential pair of transistors M_1 and M_2 with a current source I_0 at the top. The gate voltages are V_T and $V_T + \Delta V_T$. The output currents are I_0 and $I_0 + \Delta I$. A KVL loop is indicated around the gates.

So, v_{os} is called the input referred offset voltage and i_{os} is the input referred offset current.

Please note that since we are talking about statistical quantities, it is quite possible for v_{os} and i_{os} to be correlated. I only say may because it is also possible for them to be completely uncorrelated. So, it is possible for them to be wholly or partially correlated. And of course, because we are now dealing with statistical quantities if uncorrelated or rather for uncorrelated quantities, you need to use squared quantities in your analysis.

In other words if 2 quantities if your trying to find the offset voltage due to a random mismatch or a random variation in the resistance, and transistor V_T these 2 would move independently and therefore, you need to look at the operate in terms of squared quantities. Now let us go back to an to do our example we will do an example of a current mirror circuit. So, let us say I am going to take current mirror, and analyze it is output current for mismatch. So, this is my input transistor, and ideally my output current should be I_{naught} assuming that M_1 and M_2 are identical.

Now, what I am going to do is, I am going to assume variation in certain parameters, for the purposes of this particular example I am going to assume that there is mismatch only in the threshold voltage of the 2 devices. So, let us say this device has a threshold voltage V_T and M_2 has a threshold voltage which is V_T plus ΔV_T . Now the minute I do this the first thing I know is that the both the devices have the same gate source voltages purely by applying KVL around the slope. So, what I know is V_{GS1} is the same as V_{GS2} .

But now because the threshold voltage is a different there will be a mismatch in the output current. So, I will now say that the output current is I_{naught} plus ΔI , I need to find out the distribution of ΔI in terms of the distribution of ΔV_T . If you do that for this particular circuit the your job is done. So, how do I find out the value of ΔI ? So, the first thing I can do is assume that this ΔV_T is small; obviously, nominally the 2 devices better be identical and therefore, any distribution is fairly tightly controlled.

So, I can assume that ΔV_T is small. So, that is the other assumption I am going to make. Once I do this it should be now pretty straight forward because now ΔV_T or rather ΔV_t is going to cause a change in ΔI .

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$$I_D = \frac{1}{2} \mu_n C_{ox} \left(\frac{W}{L}\right) (V_{GS} - V_T)^2$$

$$\frac{\partial I_D}{\partial V_{GS}} = g_m ; \quad \frac{\partial I_D}{\partial V_T} = -\frac{\partial I_D}{\partial V_{GS}} = -g_m$$

$$\Delta I = -g_m \Delta V_T \Rightarrow \frac{\Delta I}{I_0} = -\frac{g_m \Delta V_T}{I_0}$$

$$r_{\frac{\Delta I}{I_0}}^L = \frac{g_m^2}{I_0^2} \cdot r_{V_T}^2 = \frac{g_m^2}{I_0^2} \cdot \frac{A_{V_T}^2}{W \cdot L}$$

So, maybe if I write down the equations it will be a little bit clearer before I write down the final quantity. So, I know this is the basic expression, I know that $\frac{\partial I_D}{\partial V_{GS}}$ is the transconductance of the Mosfet which is g_m , but in this particular case I need to find out $\frac{\partial I_D}{\partial V_T}$.

Now, looking at a equation it should be clear to you that this is the negative of $\frac{\partial I_D}{\partial V_{GS}}$ which is minus g_m . Therefore, I can say that for small ΔV_T the output the change in output current ΔI should be equal to minus g_m times ΔV_T . Now what is this negative sign mean for us? What this is telling us is that if V_T has a larger threshold voltage for the same V_{GS} its current will be smaller in other words ΔI will be negative. If ΔV_T is positive ΔI will be negative and vice versa. So, that is what that negative sign is telling us.

This is well and good, but this is for a particular device for a particular value of ΔV_T , I now need to find out what the distribution of the ΔI is. So, to do that I first need to find out the relative value of this, I need to find out $\frac{\Delta I}{I_0}$. So, for a given value of bias current what is the distribution of $\frac{\Delta I}{I_0}$. This is of course, minus $g_m \Delta V_T$ by I_0 and. So, let me rearrange this to.

Once I know this what I actually want to find is the distribution. So, I am going to find out $\sigma_{\frac{\Delta I}{I_0}}^2$. This is actually what I want I want to find out either the standard deviation or the variance, so that I can find out how tight the

distribution is of the output current relative to I_0 of course. So, this σ^2 $\frac{\Delta I}{I_0}$ is now going to be g_m^2 by I_0^2 times $\sigma^2 V_T$. And now what is $\sigma^2 V_T$ this is nothing, but g_m^2 by I_0^2 times $\frac{A V_T^2}{w L}$.

Now, this is telling us that for a given a V_T in a particular process, if you increase the area the relative value if you increase the area of the device, the relative effect on ΔI become smaller. For a larger bias current this affect become smaller and so on right. Please also note that you have actually lost the sign the negative sign that you originally had. That is because once you look at the titles of the distribution itself, the actual dependence of ΔI on ΔV_T no longer matters; what you really care about are the mean and variance of the this of the Gaussian distribution itself, at that point you do not care about this negative particular negative sign.